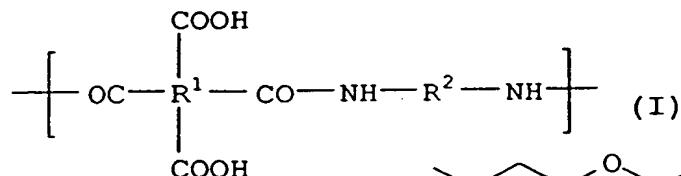


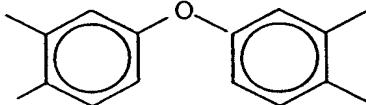
Abstract:

There are disclosed a photosensitive resin composition which comprises

5 (A) a polyamic acid having recurring units represented by the formula (I):



15 wherein R^1 represents



; and R^2

20 represents a divalent organic group, and

(B) an acryl compound having an amino group,
and also a photosensitive resin composition for an
i-line stepper which further comprises a photoinitiator in
addition to the photosensitive resin composition.